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Prof. Stacey F. Bent

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Stacey F. Bent is the Jagdeep and Roshni Singh Professor at Stanford University, where she is Professor of Chemical Engineering and Professor, by courtesy, of Chemistry, of Materials Science and Engineering, and of Electrical Engineering. She also currently serves as Vice Provost for Graduate Education and Postdoctoral Affairs. Bent obtained her B.S. degree in chemical engineering from UC Berkeley and her Ph.D. degree in chemistry from Stanford, and she was a postdoctoral fellow at AT&T Bell Laboratories. She was an assistant professor at New York University before moving to Stanford in 1998. Bent's research interests are in the understanding of surface chemistry and materials synthesis and the application of this knowledge to a variety of problems in sustainable energy, semiconductor processing, and nanotechnology. Her group's research on atomic layer deposition (ALD) ranges from fundamental mechanistic studies, to area selective ALD, to applications in solar cells, fuel cells, catalysts, and batteries. Bent has published nearly 300 peer-reviewed papers, holds 6 patents, and has presented over 330 invited talks. She has supervised 50 Ph.D. students and 25 postdoctoral scholars. Bent was elected to the U.S. National Academy of Engineering in 2020. She is also a Fellow of the American Chemical Society (ACS) and the American Vacuum Society (AVS). She is the recipient of the 2018 ACS Award in Surface Chemistry, the 2020 SRC Technical Excellence Award, and the 2021 ALD Innovator Award, the highest recognition in the ALD community. In 2021, she also was honored with the Braskem Award for Excellence in Materials Engineering and Science from the American Institute of Chemical Engineers (AIChE).